

ABSTRACT
FERROMAGNETIC MATERIAL SPUTTERING TARGET

5 Provided is a ferromagnetic material sputtering target comprising a
metal having a composition that Cr is contained in an amount of 20 mol% or
less, Ru is contained in an amount of 0.5 mol% or more and 30 mol% or less,
and the remainder is Co, wherein the target has a structure including a base
metal (A) and, within the base metal (A), a Co-Ru alloy phase (B) containing
10 35 mol% or more of Ru. The present invention provides a ferromagnetic
material sputtering target that can improve leakage magnetic flux to allow
stable discharge with a magnetron sputtering apparatus.

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